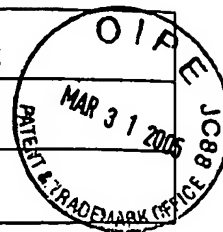


|  |  |                                       |                               |
|--|--|---------------------------------------|-------------------------------|
| Substitute Form PTO-1449<br>(Modified)   | U.S. Department of Commerce<br>Patent and Trademark Office | Attorney's Docket No.<br>10559-879001 | Application No.<br>10/688,306 |
| <b>Information Disclosure Statement<br/>by Applicant</b><br>(Use several sheets if necessary)<br>(37 CFR §1.98(b)) |  | Applicant<br>Yan Borodovsky           |                               |
|  |  | Filing Date<br>October 17, 2003       | Group Art Unit<br>2851        |



| U.S. Patent Documents |           |                 |                  |          |       |          |                            |
|-----------------------|-----------|-----------------|------------------|----------|-------|----------|----------------------------|
| Examiner Initial      | Desig. ID | Document Number | Publication Date | Patentee | Class | Subclass | Filing Date If Appropriate |
|                       | AA        |                 |                  |          |       |          |                            |
|                       | AB        |                 |                  |          |       |          |                            |
|                       | AC        |                 |                  |          |       |          |                            |
|                       | AD        |                 |                  |          |       |          |                            |

| Foreign Patent Documents or Published Foreign Patent Applications |           |                 |                  |                          |       |          |             |    |
|---|-----------|-----------------|------------------|--------------------------|-------|----------|-------------|----|
| Examiner Initial  | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Translation |    |
|   |           |                 |                  |                          |       |          | Yes         | No |
|   | AE        |                 |                  |                          |       |          |             |    |
|   | AF        |                 |                  |                          |       |          |             |    |
|   | AG        |                 |                  |                          |       |          |             |    |

| Other Documents (include Author, Title, Date, and Place of Publication) |           |  |
|---|-----------|--|
| Examiner Initial  | Desig. ID | Document   |
| PA  | AH        | M. Fritze, et al., "Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 19(6):2366-2370, Nov/Dec 2001.                    |
| PA  | AI        | J.A. Hoffmagle, et al., "Liquid immersion deep-ultraviolet interferometric lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 17(6):3306-3309, Nov/Dec 1999.   |
| PA  | AJ        | Marc D. Levenson, et al., "Exposing the DUV SCAAM - 75 nm Imaging on the Cheap!", <i>Proc. of SPIE: Design, Process Integration, and Characterization for Microelectronics</i> , 4692:288-297, March 2002.                             |
| PA  | AK        | Alex K. Raub, et al., "Deep UV immersion interferometric lithography", <i>Proc. of SPIE: Optical Microlithography XVI</i> , 5040:667-678, Feb. 2003.   |
| PA  | AL        | Bruce W. Smith, et al., "Water immersion optical lithography at 193 nm", <i>J. Microlith., Microfab., Microsyst.</i> , 3(1):44-51, Jan. 2004.  |
| PA  | AM        | Akiyoshi Susuki, et al., "Multilevel imaging system realizing $k_1 \approx 0.3$ lithography", <i>Proc. of SPIE: Optical Microlithography XII</i> , 3679:396-407, Mar. 1999.  |
| PA  | AN        | M. Switkes, et al., "Extending optics to 50 nm and beyond with immersion lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 21(6):2794-2799, Nov/Dec 2003.   |
| PA  | AO        | Brian Tyrrell, et al., "Investigation of the physical and practical limits of dense-only phase shift lithography for circuit feature definition", <i>J. Microlith., Microfab., Microsyst.</i> , 1(3):244-252, Oct. 2002.               |
| PA  | AP        | Saleem H. Zaidi, et al., "Multiple exposure interferometric lithography", <i>Proc. of SPIE: Optical Microlithography VII</i> , 2197:869-875, Mar. 1994.  |
| PA  | AQ        | M. Fritze, et al., "Preprint of poster presentation entitled "High-Throughput Hybrid Optical Maskless Lithography: All-Optical 32-nm Node Imaging," Presented at SPIE Microlithography 2005, San Jose, California, USA, March 3, 2005. |

|  |                           |
|--|---------------------------|
| Examiner Signature<br>   | Date Considered<br>8/3/05 |
| EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. |                           |

|  |  |                                       |                               |
|--|--|---------------------------------------|-------------------------------|
| Substitute Form PTO-1449<br>(Modified)   | U.S. Department of Commerce<br>Patent and Trademark Office | Attorney's Docket No.<br>10559-879001 | Application No.<br>10/688,306 |
| <b>Information Disclosure Statement<br/>by Applicant</b><br>(Use several sheets if necessary)<br>(37 CFR §1.98(b)) |  | Applicant<br>Yan Borodovsky           |                               |
|  |  | Filing Date<br>October 17, 2003       | Group Art Unit<br>2851        |

### U.S. Patent Documents

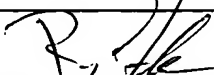
| Examiner Initial | Desig. ID | Document Number | Publication Date | Patentee       | Class | Subclass | Filing Date If Appropriate |
|------------------|-----------|-----------------|------------------|----------------|-------|----------|----------------------------|
| PA               | AA        | 2005/0073671    | 04/2005          | Borodovsky     |       |          |                            |
| PA               | AB        | 2005/0074698    | 04/2005          | Borodovsky     |       |          |                            |
| PA               | AC        | 2005/0085085    | 04/2005          | Borodovsky     |       |          |                            |
| PA               | AD        | 2005/0088633    | 04/2005          | Borodovsky     |       |          |                            |
| PA               | AE        | 5,759,744       | 06/1998          | Brueck, et al. |       |          |                            |
| PA               | AF        | 6,233,044       | 05/2001          | Brueck, et al. |       |          |                            |
|                  | AG        |                 |                  |                |       |          |                            |
|                  | AH        |                 |                  |                |       |          |                            |
|                  | AI        |                 |                  |                |       |          |                            |
|                  | AJ        |                 |                  |                |       |          |                            |
|                  | AK        |                 |                  |                |       |          |                            |

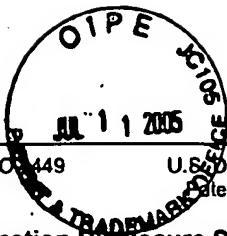
### Foreign Patent Documents or Published Foreign Patent Applications

| Examiner Initial | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Translation |    |
|------------------|-----------|-----------------|------------------|--------------------------|-------|----------|-------------|----|
|                  |           |                 |                  |                          |       |          | Yes         | No |
|                  | AL        |                 |                  |                          |       |          |             |    |
|                  | AM        |                 |                  |                          |       |          |             |    |
|                  | AN        |                 |                  |                          |       |          |             |    |
|                  | AO        |                 |                  |                          |       |          |             |    |
|                  | AP        |                 |                  |                          |       |          |             |    |

### Other Documents (include Author, Title, Date, and Place of Publication)

| Examiner Initial | Desig. ID | Document |
|------------------|-----------|----------|
|                  | AQ        |          |
|                  | AR        |          |
|                  | AS        |          |
|                  | AT        |          |

|  |                               |
|--|-------------------------------|
| Examiner Signature    | Date Considered <u>8/3/05</u> |
| EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. |                               |

Sheet 1 of 1

|  |  |  |                                      |
|--|--|--|--------------------------------------|
| Substitute Form PTO-1449<br>(Modified)<br><br><b>Information Disclosure Statement<br/>by Applicant</b><br>(Use several sheets if necessary)<br><br>(37 CFR §1.98(b)) | U.S. Department of Commerce<br>Patent and Trademark Office | Attorney's Docket No.<br><b>10559-879001</b> | Application No.<br><b>10/688,306</b> |
|  | Applicant<br><b>Yan Borodovsky</b>                         |  |                                      |
|  | Filing Date<br><b>October 17, 2003</b>                     | Group Art Unit<br><b>2851</b>                |                                      |

| U.S. Patent Documents |           |                 |                  |                   |       |          |                            |
|-----------------------|-----------|-----------------|------------------|-------------------|-------|----------|----------------------------|
| Examiner Initial      | Desig. ID | Document Number | Publication Date | Patentee          | Class | Subclass | Filing Date If Appropriate |
| <i>Pt</i>             | AA        | 5,759,744       | June 2, 1998     | Brueck, et al.    |       |          |                            |
| <i>Pt</i>             | AB        | 5,415,835       | May 16, 1995     | Brueck, et al.    |       |          |                            |
| <i>Pt</i>             | AC        | 5,328,807       | July 12, 1994    | Tanaka, et al.    |       |          |                            |
| <i>Pt</i>             | AD        | 6,553,562       | April 22, 2003   | Capodieci, et al. |       |          |                            |
|                       | AE        |                 |                  |                   |       |          |                            |
|                       | AF        |                 |                  |                   |       |          |                            |
|                       | AG        |                 |                  |                   |       |          |                            |
|                       | AH        |                 |                  |                   |       |          |                            |
|                       | AI        |                 |                  |                   |       |          |                            |
|                       | AJ        |                 |                  |                   |       |          |                            |
|                       | AK        |                 |                  |                   |       |          |                            |

| Foreign Patent Documents or Published Foreign Patent Applications |           |                 |                  |                          |       |          |             |    |
|---|-----------|-----------------|------------------|--------------------------|-------|----------|-------------|----|
| Examiner Initial  | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Translation |    |
|   |           |                 |                  |                          |       |          | Yes         | No |
| <i>Pt</i>   | AL        | EP 0855623      | July 29, 1998    | EP                       |       |          |             |    |
| <i>Pt</i>   | AM        | WO 98/32054     | July 23, 1998    | PCT                      |       |          |             |    |
|   | AN        |                 |                  |                          |       |          |             |    |
|   | AO        |                 |                  |                          |       |          |             |    |
|   | AP        |                 |                  |                          |       |          |             |    |

| Other Documents (include Author, Title, Date, and Place of Publication) |           |  |
|---|-----------|--|
| Examiner Initial  | Desig. ID | Document   |
| <i>Pt</i>   | AQ        | Ishibashi, et al., "AFM Lithography Combined with Optical Lithography", <i>IEEE Microprocesses and Nanotechnology Conference 2000</i> , pp. 192-193 (July 2000). |
| <i>Pt</i>   | AR        | Martin, et al., "Ordered Magnetic Nanostructures: Fabrication and Properties", <i>J. Magnetism and Magnetic Materials</i> , 256(1-3):449-501 (January 2003).     |
|   | AS        |  |
|   | AT        |  |

|  |                                  |
|--|----------------------------------|
| Examiner Signature<br><i>[Signature]</i>   | Date Considered<br><i>8/7/05</i> |
| EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. |                                  |

Substitute Disclosure Form (PTO-1449)